

**AMENDMENTS TO THE CLAIMS**

1-3. (canceled)

4. (currently amended) The resist development processor according to Claim [[1]] 5 characterized in that said development processing chamber is provided with a temperature regulator for ensuring that a high pressure gas in said development processing chamber is discharged, with the temperature of gas in said development processing chamber maintained above the temperature of critical point, thereby allowing the gas to be discharged without being liquefied.

5. (currently amended) [[The]] A resist development processor ~~according to Claim 1~~ comprising:

a development processing chamber for storing a resist substrate having an exposed resist on the substrate and for developing the exposed resist by means of a development solvent comprising a supercritical fluid; and

a supercritical fluid container for storing a supercritical fluid, said supercritical fluid container being connected to said development processing chamber through a valve; and

wherein said processor is characterized by comprising resist substrate holding means that prevents said development solvent in liquid state from coming into contact with said resist substrate, when said liquid development solvent is introduced into said development processing chamber.

6. (canceled)

7. (currently amended) The resist development processor according to Claim

[[1]] 5 characterized in that said supercritical fluid container is connected through a valve and a high pressure force supply pump, in contact with said liquid of the liquid container for storing said liquid development solvent.

8. (canceled)

9. (currently amended) The resist development processor according to Claim [[1]] 5 further comprising a temperature regulator for regulating the difference in the temperature of said development solvent from each vessel, supplied to said development processing chamber.

10-16. (canceled)